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Peculiarities of Voltammetry and Dissociation of Hydroxycarboxylic Acids

Elene -. Kvaratskhelia[1] and Ramaz Kvaratskhelia[1]

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[1] R.Agladze Institute of Inorganic Chemistry and Electrochemistry

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Abstract

The study of voltammetry of two hydroxycarboxylic acids: D-tartaric and citric acids at the electrodes from Pt, Cu, Ta, Cu-Hg and alloys of Cd with Sn, Ni, Hg, In in aqueous solutions shows that these acids in all cases form the hydrogen ions discharge process waves. With the aid of the suggested by authors method the values of the degrees of dissociation of various hydroxycarboxylic acids (D-, L-, DL-, meso-tartaric, citric, malic acids) in the concentration range 0.0001-0.01M and the pH range 1-4 were calculated.

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